

# Electron heating in capacitively coupled discharges and reactive gases

Gerhard Franz<sup>a)</sup>

*Munich University of Applied Sciences, D-80335 Munich, Germany*

Michael Klick<sup>b)</sup>

*Advanced Semiconductor Instruments, D-12459 Berlin, Germany*

(Received 13 October 2004; accepted 13 May 2005; published 27 June 2005)

The effective collision frequency  $\nu_{\text{eff}}$  of electrons in capacitively driven discharges of Ar/Kr, Cl<sub>2</sub> and BCl<sub>3</sub> has been investigated using self-excited electron resonance spectroscopy. The most prominent features are the steep increase of  $\nu_{\text{eff}}$  at low power inputs in all three gases and a slight but systematic decrease of  $\nu_{\text{eff}}$  versus  $p$  for Ar/Kr and BCl<sub>3</sub> over the whole pressure range investigated. At medium pressures, the effective collision rate  $\nu_{\text{eff}}$  in Cl<sub>2</sub> increases by 2 orders of magnitude which is a clear manifestation for the transition from stochastic to ohmic heating. These features have been correlated with data gained with a  $V(I)$  probe. The dependence of the ohmic discharge resistance is mainly determined by the drastic change of  $\nu_{\text{eff}}$  rather than by the variation of electron density  $n_e$ . © 2005 American Vacuum Society. [DOI: 10.1116/1.1947201]